

<b>Notice of References Cited</b>	Application/Control No. 09/925,466	Applicant(s)/Patent Under Reexamination YAMAGIWA ET AL.	
	Examiner Mohammad A. Siddiqi	Art Unit 2154	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,741,265	05-2004	Ghosh et al.	715/751
	B	US-6,757,715	06-2004	Philyaw, Jeffry Jovan	709/210
	C	US-6,151,101	11-2000	Okino, Teruaki	355/53
	D	US-6,601,108	07-2003	Marmor, Eliyahu	709/246
	E	US-5,952,133	09-1999	Nakasuji, Mamoru	430/22
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Automated Evaluation of Critical Features in VLSI Layouts Based on Photolithographic Simulation By Chaitali Sengupta, IEE transaction on Semiconductor Manufacturing, Vol, 10 4, November 1997.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.